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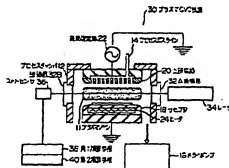
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(54) PLASMA TREATING DEVICE

(57) Abstract:

PROBLEM TO BE SOLVED: To provide a plasma treating device in which the cleaning of the inner wall of a process chamber is effectively executed as appropriate.

SOLUTION: In a plasma treating device 30, the wall face opposite to a chamber wall is provided with a pair of penetrating windows 32A and B respectively arranged at the positions directly on a straight line and a laser 34 radiating a laser light from either penetrating window 32A toward the other penetrating window 32B. Moreover, it is provided with a photosensor 36 detecting the optical intensity of the laser light emitted from the other penetrating window 32B, transforming it to an electric signal and outputting it and a primary arithmetic means 38 obtaining the secular variation of the optical intensity outputted from the photosensor 36. Moreover, the plasma treating device 30 is provided with a secondary arithmetic means 40 judging the effect of cleaning film adhered to the chamber wall based on the secular variation of the optical intensity obtd. from the primary arithmetic means 38 in accordance with the correlation between the secular variation of the optical intensity of the laser light and the film thickness of the film adhered to the chamber wall.



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